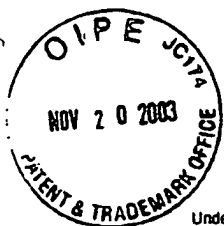


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Application No. <u>09/653,411</u>	Prepared by <u>NPB</u>	Tracking Number <u>05,895,991</u>	
Examiner-GAU <u>Eckert - 2815</u>	Date <u>3/10/04</u>	Week Date <u>1/26/04</u>	
	No. of queries <u>2</u>	<u>1PW</u>	

JACKET			
a. Serial No.	f. Foreign Priority	k. Print Claim(s)	p. PTO-1449
b. Applicant(s)	g. Disclaimer	l. Print Fig.	q. PTOL-85b
c. Continuing Data	h. Microfiche Appendix	m. Searched Column	r. Abstract
d. PCT	i. Title	n. PTO-270/328	s. Sheets/Figs
e. Domestic Priority	j. Claims Allowed	o. PTO-892	t. Other

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				Application Number	09/653,411
				Filing Date	August 31, 2000
				First Named Inventor	Whonchee Lee
				Art Unit	2815
				Examiner Name	Joseph H. Nguyen
				Attorney Docket Number	M4065.0361/P361
Sheet	1	of	3		

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Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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				Application Number	09/653,411
				Filing Date	August 31, 2000
				First Named Inventor	Whonchee Lee
				Art Unit	2815
				Examiner Name	Joseph H. Nguyen
				Attorney Docket Number	M4065.0361/P361
Sheet	2	of	3		

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		Country Code ³ -Number ⁴ -Kind Code ⁵ (if known)					
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Examiner Initials	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
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	CB	D'HEURLE, F.M. and K.C. PARK, IBM Technical Disclosure Bulletin, Electrolytic Process for Metal Pattern Generation, Vol. 17, No. 1, pp. 271-272, June 1974, XP-002235691, NN 7406271.	
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				Filing Date	August 31, 2000
				First Named Inventor	Whonchee Lee
				Group Art Unit	2815
				Examiner Name	Joseph H. Nguyen
Sheet	3	of	3	Attorney Docket Number	M4065.0361/P361

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